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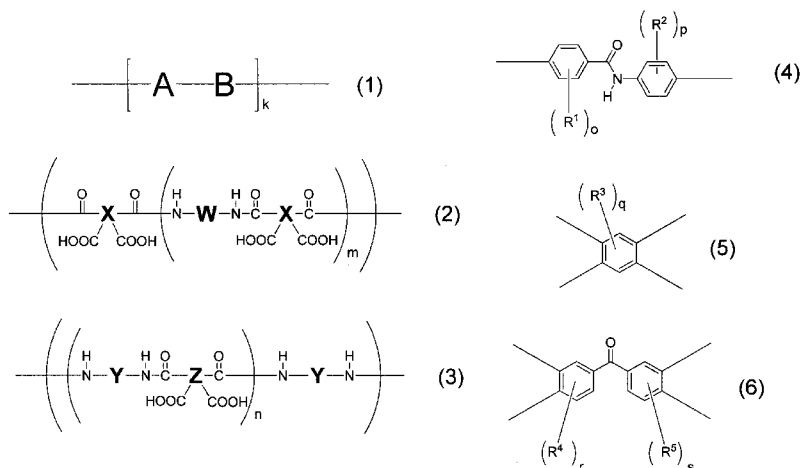
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(54) Title: RESIN COMPOSITION AND MANUFACTURING PROCESS THEREFOR

(54) 発明の名称: 樹脂組成物およびその製造方法



(57) Abstract: Provided is a polyamic acid resin composition which exhibits excellent storage stability and which can yield, through heat treatment, a film having excellent heat resistance. The polyamic acid resin composition is characterized by comprising (a) a polyamic acid which comprises structures represented by general formula (1) in an amount of at least 80% of all the repeating units and (b) a solvent. In general formula (1), A is a polyamic acid block represented by general formula (2); B is a polyamic acid block represented by general formula (3); and k is a positive integer. In general formula (2), Ws are divalent organic groups each having two or more carbon atoms, and are mainly composed of divalent organic groups represented by general formula (4); Xs are tetravalent organic groups each having two or more carbon atoms, exclusive of the groups represented by general formulae (5) and (6), while in general formula (3), Ys are divalent organic groups each having two or more carbon atoms, exclusive of the groups represented by general formula (4); Zs are tetravalent organic groups each having two or more carbon atoms, and are mainly composed of tetravalent organic groups represented by general formula (5) or (6). In general formulae (2) and (3), ms and ns are positive numbers respectively, and may be respectively different among blocks. In general formulae (4) to (6), R¹ to R⁵ may be each a single monovalent C₁₋₁₀ organic group or a mixture of different monovalent C₁₋₁₀ organic groups; o and p are each an integer of 0 to 4; q is an integer of 0 to 2; and r and s are each an integer of 0 to 3.

(57) 要約:

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WO 2012/043186 A1